Overview

- Review of the Goddard method
- Update on instrument/detector evolution (a purely phenomenological approach)
- Characterization of the soft proton flares (spectral shape and spatial distributions)
- Testing the stability of this method (by looking at pointings with multiple obsids)

Method Review: Philosophy

- Emission from the Galactic ISM fills the FOV
 - Sufficiently faint that it must be summed over large regions in order to produce a good spectrum
- The same is true of extended extragalactic emission (e.g. galaxies & clusters)
- Background subtraction method must provide good statistics over large regions of the FOV
- but still be sensitive to the small-scale variations in the detector

• The corner pixels are a measure of the particle background

- The corner pixels are a measure of the particle background
- There are not enough counts in the corner pixels of a single observation for a robust characterization of the background...
- ...need to find some way of using corner data from other observations...
- ...need to characterize the temporal variations of the corner spectra.

Method Review: Corner Data

- The Entire Public Archive, Revs 25-1128
 - 3500 observations, 8100 observation segments
 - 76 Ms/MOS camera
- Remove CalClosed and badly flared data
 - 2500 observation segments/MOS camera
 - 44 Ms/MOS camera
- 34% of MOS data affected by flares



For each obsid we formed a histogram of the rate, set the "quiescent level" to mean rate, and removed periods >3 above quiescent level.



3 Parameters for the Spectral Shape

Rate: 0.3-10.0 keV Hardness: 2.5-5.0/0.4-0.8 keV PL Index 5-12 keV

The mean corner spectrum





- Variation in the Hardness is greater than statistical: Hardness is temporally variable
- Variation in Power Law Index is statistical



From the database of corner data, extract more data with similar rates and hardness.



Step 1: Augmentation

Since the mean spectrum varies from chip-to-chip, augmentation must be done on chip-by-chip basis.

- The background spectrum measured by the corner data need r measured within t
- The instrumental particularly strong





The continuum also varies strongly

Step 2: Correct spectrum to the FOVAssume that temporal variations affect the corner pixels and the FOV in a similar manner.

The background spectrum in the observation FOV is then given by

<u>Obs. Corner spectrum*FWC FOV spectrum</u> FWC Corner spectrum

Step 2: Correct spectrum to the FOV

- Chip 1 is a special case corner data must be constructed from a subset of corner data for MOS 2
 the other chips
 - MOS1 use 2, 3, 6, & 7
 - MOS2 use 3, 4, & 7



Method Review: FWC Data

- The Entire Public Archive
- For normal chip states
 - 60-85 observation segments
 - -0.7-1.1 Ms of exposure
 - $-1.5-2.3 \times 10^{5}$ counts
- For anomalous chip states
 - ~10 observation segments
 - 60-200 ks of exposure
 - $-1.6-6.2 \times 10^4$ counts

Step 3: Ignore the Al and Si lines Slight shifts in strong P-Cygni 10-11 Therefore interpola Rate (counts/s/channel) ՙ႞ՇՎՆՆฦի forming the bac Fit the Al and Si lin 10^{-12} spectrum

 10^{-13}

Energy (keV)

10

Implementation:

- Originally: Perl scripts calling SAS tasks, IDL routines for light curve cleaning and background spectrum construction (mine)
- Now: Perl scripts calling SAS tasks,
 FORTRAN routines for light curve cleaning and background spectrum construction (Snowden)
- Soon: Perl scripts calling SAS tasks (Perry)





(0.3-10.) keV

- Not all chips are well behaved...
- MOS1-4, MOS1-5, MOS2-2, MOS2-5
 - anomalous states occur at different times
 - always characterized by high rates and low hardness



- MOS1-4, MOS1-5, MOS2-2, MOS2-5
 - always characterized by high rates and low hardness due to low energy "plateau"



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 - "extra" component somewhat localized for some <u>chips</u>



0.3-0.8 keV

- MOS1-4, MOS1-5, MOS2-2, MOS2-5
 - always characterized by high rates and low hardness due to low energy "plateau"
 - "extra" component somewhat localized for some chips, but not so clear in other cases





enomenology

OS2-2, MOS2-5 newhat localized for some in other cases ate does not generally



- Summary of States
 - S: "standard state"
 - V: "verification" : 1-4, 2-2, 2-5 for Rev<41.5
 - H: "high":1-4, 1-5, 2-5, detectable in corner pixels
 - A: "anonymous": 1-4, not detectable in corner pix.
 - No other chip has yet been detected in A state
 - But since A state can only be detected in FWC data...
- Need to understand what causes these states
 - Are there detector parameters that can be used to detect these states independently?
 - Particularly important for the A states!

- Handling multiple states
 - V state does not have enough effected data to justify significant effort
 - H state FWC data does exist, poor for 1-4 & 1-5
 - A state FWC data OK for 1-4 (not great)
- Modifications to ESAS
 - Detect chip state first
 - Extract appropriate state FWC data
 - Augmentation careful to exclude data from the wrong state
 - For now 1-4 is caveat emptor

Soft Proton Flare Characterization





kuntz 30-Apr-2006 11:4

- Use the entire public archive
- For each obsid, run light-curve cleaning
- If light-curve cleaning successful
 - Extract spectrum from full FOV for flare-free int.
 - Extract spectrum from full FOV from flare int.
 - Spectrum=flare-non-flare* $t_{flare}/t_{non-flare}$
 - since flare spectral shape depends upon the strength of the flare, select only weak flares for this analysis
 - Assumes that s.p. flare is additive.

- Characterize (8.0-10.0 keV)
- Wide range o
 - Not clear wh
 - Moot point





• Best fit <mark>╞<u>┠═┖╌╏┲╌┰╊</u>┨═╾╢┅╝╢╲_┚╔╴╬╿</mark> A₀ex 3 Fun ᠊᠋<u>᠋᠊</u>᠋᠋᠋᠋᠆ᢞ᠊ᡡᡙᡡᢇ᠋ᢪᡊᡀᠬᡐᢧᡢ<mark>ᠰ᠋᠕ᠵᢋᢤᢢᡨᢤᡘᢩ</mark>ᡇ where Log10(Relative Flux) which provides the a_i and b_i nee but has the prot implemented

Log₁₀(Energy/keV)



• Spatial distribution determined in same way as the spectrum but with bright point sources explicitly removed from the images







- Spectro-spatial variation
 - Spectrum becomes steeper with radius
 - Little difference between chips at the same radius
 - (with the exception of the "hot" spot on MOS1-2)



- If fitting multiple regions (i.e., a cluster)
 - The normalization of the S.P. contamination must be allowed to vary with radius.
 - The spectral shape of the S.P. contamination must be allowed to vary with radius.

- How good is the method?
 - Small number statistics for corner data
 - Marginal statistics for FWC corrections
 - Introducing systematics at low energies?
- Test
 - Find directions with multiple obsids
 - Divide MOS1 and MOS2 spectra by responses
 - Sum and smooth
 - Compare
- Chose 8 high b fields with a total of 40 obsids

Lowest spectrum set as fiducial
 Dotted = uncertainty in difference



- Lowest spectrum set as fiducial
- Statistics: of 40 obsids
 - 5-8 show signs of SWCX
 - 1 shows strong SPC
 - Several show minor SPC
- Differences between spectra (other than those due to SWCX) consistent within uncertainties



